

$(1/3) \times VDD$ -to- $(3/2) \times VDD$ Wide-Range I/O Buffer Using 0.35- μm 3.3-V CMOS Technology

Chi-Chun Huang, *Student Member, IEEE*, Tzung-Je Lee, Wei-Chih Chang, and Chua-Chin Wang, *Senior Member, IEEE*

Abstract—A 0.9/1.2/1.8/2.5/3.3/5.0-V wide-range input/output buffer carried out using a typical complementary metal-oxide-semiconductor (MOS) 2P4M 0.35- μm process is proposed in this brief. An input buffer with a logic calibration circuit is used for receiving a low voltage signal. A novel floating n-well circuit is employed to remove the body effect at the output p-channel MOS (PMOS). Moreover, a dynamic driving detector is included to equalize the turn-on voltages for the output PMOS and n-channel MOS transistors. The worst-case duty cycle of the output signal can then be 54.2% in a low-voltage mode. The maximum output frequency of the proposed design is measured to be 17.9/27.9/35.3/70.1/79.2/60.0 MHz for VDDIO = 0.9/1.2/1.8/2.5/3.3/5.0 V, respectively. The power consumption is 553 nW at the worst simulation case of [SS, 100 °C] and 330 nW by on-silicon measurement.

Index Terms—Floating n-well, gate tracking, input/output (I/O) buffer, level converter, mixed-voltage tolerant.

I. INTRODUCTION

RAPID development of semiconductor technologies causes the dimensions and supply voltages of transistors to be quickly scaled down to reduce the area cost and power consumption. During such an evolution, many chips on a printed-circuit-board-based system are fabricated by different technologies. Moreover, voltage difference might exist among different buses in one system. A signal voltage-level compatibility problem appears when those chips are used to communicate with one another since the voltage levels of these chips might be different. Traditional I/O buffers are no longer adequate to these different voltage-level signals due to the hazards of gate-oxide overstress, hot-carrier degradation, and unwanted leakage current paths [1]–[4]. By contrast, mixed-voltage I/O buffers are considered as a better solution to reduce the time-to-market than extra off-chip level shifters. Three types of mixed-voltage I/O buffers have been reported in prior works.

Type-I mixed-voltage I/O buffer is able to receive the signals at $2 \times VDD$, [3]–[7]. By using stacked n-channel MOS

(NMOS) transistors, the gate-oxide overstress at the output NMOS transistor can be avoided when $2 \times VDD$ is received. The aforementioned stacked NMOS and leakage elimination methodologies are only activated when $2 \times VDD$ appears in the receiving mode. Thus, a Type-I mixed-voltage I/O buffer can receive the high voltage signal, but it cannot transmit a high voltage signal, let alone a $2 \times VDD$ signal.

Type-II mixed-voltage I/O buffers, which can transmit high voltage signals, were disclosed in [8]–[10]. To avoid the gate-oxide overstress, two individual stacked p-channel MOS (PMOS) and NMOS are used in the output stage. However, these designs ignore the problem of the unwanted leakage current paths when a high voltage signal is biased at the PAD in the receiving mode.

Type-III mixed-voltage I/O buffer can transmit and receive signals with high, normal, and low voltage levels (VDDH, VDD, and VDDL) by including the aforementioned methodologies [11]–[14]. However, the I/O buffer can only communicate with the signal $\approx 1/2 \times VDD$. When the supply voltage (VDDIO) is scaled down to be lower than $1/2 \times VDD$, the output signal is difficult to be pulled up to the required I/O voltage (VDDIO) due to the body effect of the output PMOS and the low turn-on voltages (V_{gs}) for the output NMOS.

This work proposes a very wide range I/O buffer using a 0.35- μm 3.3-V CMOS process, which can transmit and receive the signal of 0.9/1.2/1.8/2.5/3.3/5.0 V without any gate-oxide overstress and leakage current. The lower bound of the operating voltage is extended to be almost $0.27 \times VDD$. The output frequencies for VDDIO = 0.9/1.2/1.8/2.5/3.3/5.0 V are measured to be 17.9/27.9/35.3/70.1/79.2/60.0 MHz, respectively, at a given capacitive load of 30 pF.

II. VERY WIDE RANGE I/O BUFFER

Fig. 1(a) shows the schematic of the proposed I/O buffer. The problems of possible gate-oxide overstress and unwanted leakage current can be avoided by employing the output stage composed of stacked transistors and dynamic gate bias generator, gate tracking, and floating n-well circuit.

For operation at $VDDIO \leq (1/2) \times VDD$, there are two problems to be conquered. First, the output PMOS PM202 has a body effect by using the traditional floating n-well circuit, which biases the n-well at 3.3 V in the transmitting mode for all different VDDIOs. Second, when VDDIO is biased at VDDL (= 0.9/1.2/1.8/2.5 V), the turn-on voltage supplied for the output PMOS would be smaller than that for the output NMOS, which is controlled by a 3.3-V signal DN. These two problems reduce the driving current I_{OH} such that the duty cycle of the output signal will be deviated from 50% when

Manuscript received June 10, 2009; revised October 7, 2009. Current version published February 26, 2010. This work was supported in part by the National Science Council under Grant NSC 96-2628-E-110-019-MY3, by the National Health Research Institutes under Grant NHRI-EX99-9732EI, and by the Ministry of Economic Affairs under Grant 97-EC-17-A-01-S1-104. This paper was recommended by Associate Editor A. I. Karsilayan.

The authors are with the Department of Electrical Engineering, National Sun Yat-Sen University, Kaohsiung 80424, Taiwan (e-mail: ccwang@ee.nsysu.edu.tw).

Color versions of one or more of the figures in this paper are available online at <http://ieeexplore.ieee.org>.

Digital Object Identifier 10.1109/TCSII.2010.2040311

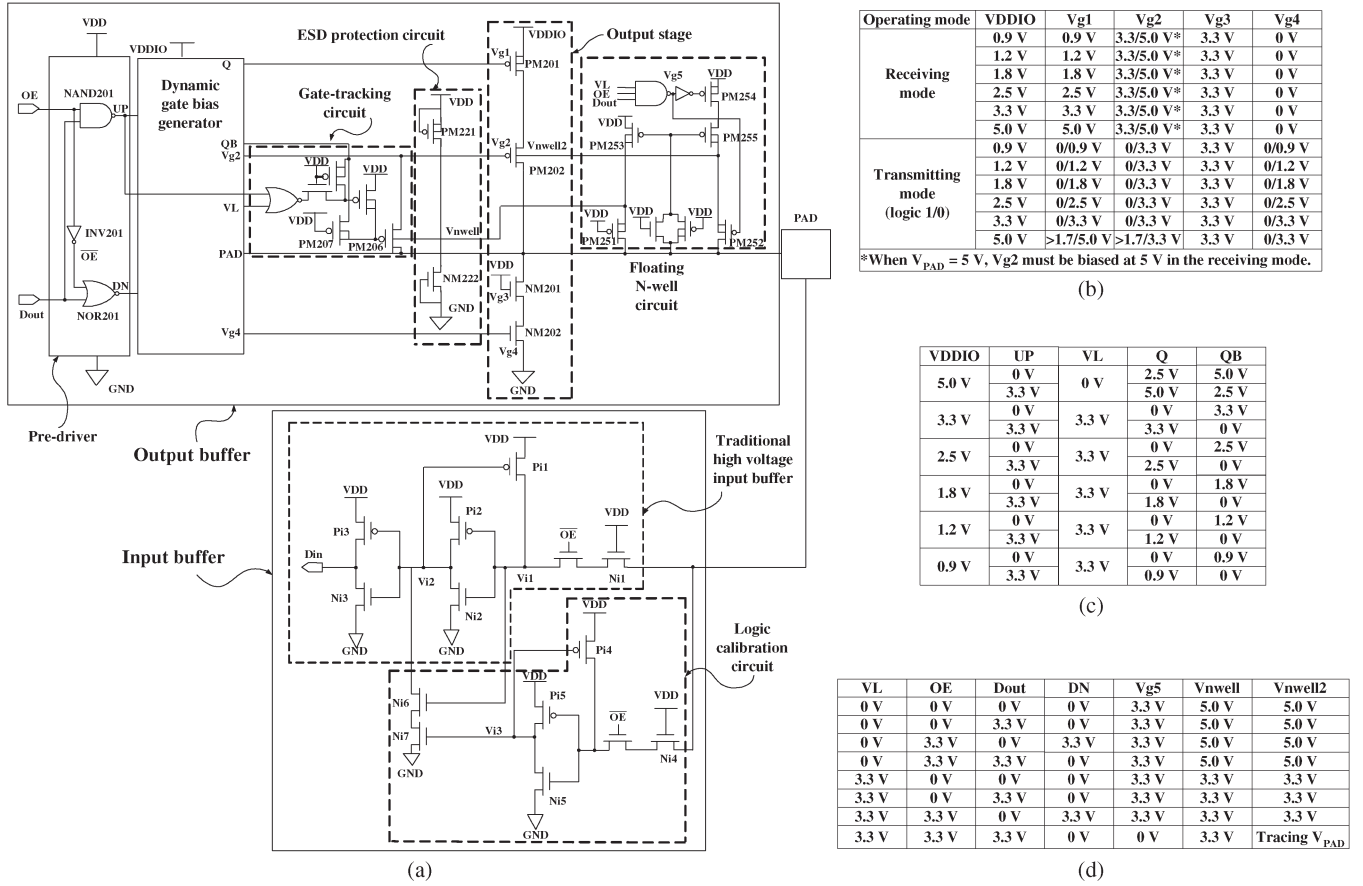


Fig. 1. Proposed mixed-voltage-tolerant I/O buffer. (a) Schematic of the proposed I/O buffer. (b) Truth table for gate voltages of the output stage. (c) Truth table for the outputs of the voltage-level converter. (d) Truth table for the outputs of the floating n-well circuit.

$VDD = VDDL$. It might cause missing codes, which should be avoided in all kinds of digital systems.

A. Theory of the Proposed I/O Buffer

The proposed design employs a new floating n-well circuit, which provides a dynamic n-well voltage (V_{nwell2}), to avoid the body effect by tracing PM202's source voltage in the transmitting mode for $VDDIO = VDDL$. Moreover, a dynamic driving detector, as shown in Fig. 2, is used to generate $Vg4$ with an amplitude of $VDDIO$ for the output NMOS when $VDDIO = VDDL$. Thus, the turn-on voltages could be equalized. Moreover, the function of gate tracking should be turned off in the transmitting mode for $VDDIO = 5.0$ V. Otherwise, the driving current of PM202 would gradually be reduced when the output signal V_{PAD} rises toward 5.0 V. Thus, the output duty cycle will be very close to 50% for all $VDDIO$ s.

On the other hand, because 1.8 V is very close to the switch point of 3.3-V logic circuits, an input buffer with a logic calibration is used to receive the signal with an amplitude less than 1.8 V.

Moreover, a dc bias required in the dynamic gate bias generator is very important for low-power operation. Many prior works use a simple MOS resistor string, which results in a tradeoff between the stability and the power consumption caused by the dc operation current. Using diode-connected MOS and charge redistribution topology might cause a penalty of circuit complexity. In this brief, a low-power clamping bias circuit with a low operation current is used to provide a stable dc voltage [11].

B. Schematic Design of the Proposed I/O Buffer

The details of each subcircuit in the proposed I/O buffer are disclosed as follows.

Pre-driver: The predriver is in charge of predriving and decoding. When $OE = 3.3$ V, the output signal $Dout$ would be transmitted. In this case, UP and DN will be both biased at 3.3 V (0 V) for $Dout = 0$ V (3.3 V). When $OE = 0$ V, the I/O buffer is in the receiving mode, and UP and DN would be biased at 3.3 and 0 V, respectively.

Output Stage: The output stage is composed of the stacked PMOS, i.e., PM201 and PM202, and the stacked NMOS, i.e., NM201 and NM202. In addition to the stacked transistor strings, the output stage requires appropriate gate bias voltages to avoid gate-oxide overstress and correctly operate for different $VDDIO$ s, as shown in the truth table in Fig. 1(b). In the receiving mode, $Vg1$ is biased at $VDDIO$ to turn PM201 off. In the mean time, $Vg2$, $Vg3$, and $Vg4$ are biased at 3.3, 3.3, and 0 V, respectively. Notably, when $V_{PAD} = 5.0$ V, $Vg2$ should be pulled to 5.0 V by the gate-tracking circuit to avoid the leakage current path through PM202. In the transmitting mode, $Vg1$ and $Vg2$ are biased at the voltage larger than 1.7 V ($= 5.0 - 3.3$ V) for $VDDIO = 5.0$ V and biased at 0 V for other $VDDIO$ s. Thus, logic 1 can be transmitted, and the gate-oxide overstress is avoided. For transmitting logic 0, $Vg4$ is biased at $VDDIO$ when $VDDIO = VDDL$ or VDD to equalize turn-on gate-source voltages for the output transistors PM201 and NM202. These gate

and V_{PAD} . V_{nwell} is similar to the traditional floating n-well voltage to trace V_{PAD} in the receiving mode. Notably, V_{nwell2} can trace V_{PAD} when transmitting logic 1, which is totally different from any prior work. Hence, the body effect on PM202 can be removed, and the driving current is enhanced. When V_{DDIO} is at V_{DDL} or V_{DD} and logic 1 is transmitted, the gate of PM252 is biased at 0 V such that V_{nwell2} is equal to V_{PAD} . Therefore, the n-well voltage of PM202 can trace its drain and source voltage such that the body effect is eliminated. At the same time, V_{nwell} is biased at 3.3 V by PM253. When 5.0 V is transmitted, the gate of PM252 is biased at 3.3 V. PM251 and PM252 would be turned on such that V_{nwell} and V_{nwell2} are both biased at 5.0 V by V_{PAD} . The leakage current paths through the parasitic diodes of PM202 and PM206 are then closed. Similarly, V_{nwell} and V_{nwell2} can be biased at 5.0 V for $V_{PAD} = 5.0$ V in the receiving mode through PM251 and PM252, respectively. For all other cases in the receiving mode, V_{nwell} and V_{nwell2} are biased at 3.3 V through PM253 and PM254, as well as PM255, respectively.

Input Buffer: The input buffer is composed of a traditional high-voltage input buffer, which can receive the input signal with a high voltage without any gate oxide overstress, and a logic calibration circuit. By properly tuning the aspects of the transistors, the traditional high-voltage input buffer can receive 1.8-V signal. However, when $V_{PAD} = 0.9$ V or 1.2 V, V_{i2} would be biased at 3.3 V, and D_{in} is at 0 V to cause a logic error since the switching voltage of the inverter, P_{i2} and N_{i2} , is higher than 1.2 V. The logic error is resolved by adding the logic calibration circuit. When $V_{PAD} = 1.2$ V or 0.9 V, V_{i3} is biased at 3.3 V to turn on N_{i7} such that V_{i2} can be pulled to 0 V by N_{i7} and the feedback loop composed of P_{i1} , P_{i2} , and N_{i2} . Then, the logic error can be corrected.

ESD Protection Circuit: Although the output stage is composed of the stacked transistors, the HBM ESD level from V_{DDIO} to PAD is still larger than most of the commercial requirements, i.e., 2 kV, by attaining the aspect ratio of $880 \mu\text{m}/0.35 \mu\text{m}$ and $216 \mu\text{m}/0.35 \mu\text{m}$ for the output PMOS and NMOS transistors, respectively. However, the ESD strength from PAD to VDD will be weak if no ESD circuit is used. Thus, a pair of gate-source-coupled transistors NM222 and PM221 is employed to improve the HBM ESD level for PAD-to-GND and PAD-to-VDD modes. Notably, the node between NM222 and PM221 need not be connected to any other node, as shown in Fig. 1(a). By tuning the aspect ratio, the ESD protection circuit will bypass the current via GND and VDD.

III. IMPLEMENTATION AND MEASUREMENT

The proposed design is implemented using a typical 0.35- μm 2P4M CMOS process. Fig. 3 shows the die photo and layout of the proposed I/O buffer, where IO1 is the proposed buffer, IO2 is the same as IO1 with several observable outputs, and IO3 does not include any ESD protection circuit for the testing purpose. The area of the proposed circuit is $0.497 \times 0.111 \text{ mm}^2$.

Fig. 4 shows the measured waveforms of V_{PAD} , V_{nwell} , V_{g2} , and V_{nwell2} in the receiving mode. When the receiving signal V_{PAD} is biased at 5.0 V, V_{nwell} , V_{nwell2} , and V_{g4} are pulled to 5.0 V by a floating n-well circuit and a gate-tracking

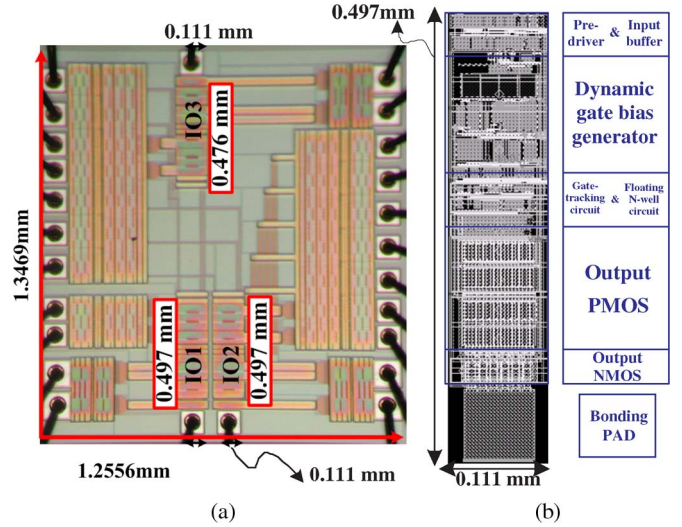


Fig. 3. Die photo and layout of the proposed design. (a) Die photo. (b) Layout.

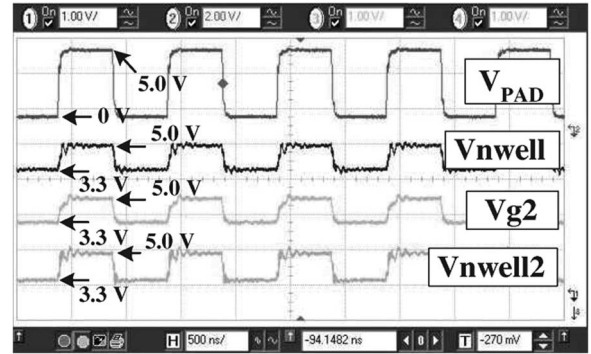


Fig. 4. Measured waveforms of V_{PAD} , V_{nwell} , V_{g2} , and V_{nwell2} in the receiving mode for a 5.0-V 1-MHz signal is given at V_{PAD} .

circuit, respectively. Thus, the unwanted leakage current paths are blocked.

Fig. 5 shows the measured full-swing waveforms of the output signal V_{PAD} at the maximum operating frequency. The maximum operating frequency for $V_{DDIO} = 0.9/1.2/1.8/2.5/3.3/5.0$ V are 17.9/27.9/35.5/70.1/79.2/60.0 MHz, respectively, given a 30-pF load. Moreover, the duty cycle are measured to be 54.2% for the worst case when $V_{DDIO} = 5.0$ V. The static power consumption is 553 nW at the worst simulation corner of the SS model and 100 °C for $V_{DDIO} = 5.0$ V [15]. Since the resolution of the measurement equipment Picotest M3500A is 100 nA and $V_{DD} = 3.3$ V, we can conclude that the max power is less than 330 nW.

Table I reveals the specification comparison of the proposed design with prior works. Because only two stacked PMOS and NMOS transistors are used in the output stage, the area is much smaller than that of [10]. In addition, the proposed design is the only one that can be applied to six different voltage modes without using any thick-oxide devices.

IV. CONCLUSION

A 0.9/1.2/1.8/2.5/3.3/5.0-V very wide range I/O buffer has been proposed in this brief. The proposed I/O buffer can provide six V_{DDIO} modes for transmitting and receiving without any gate-oxide overstress and leakage current path. By eliminating the body effect of the output PMOS and equalizing the turn-on

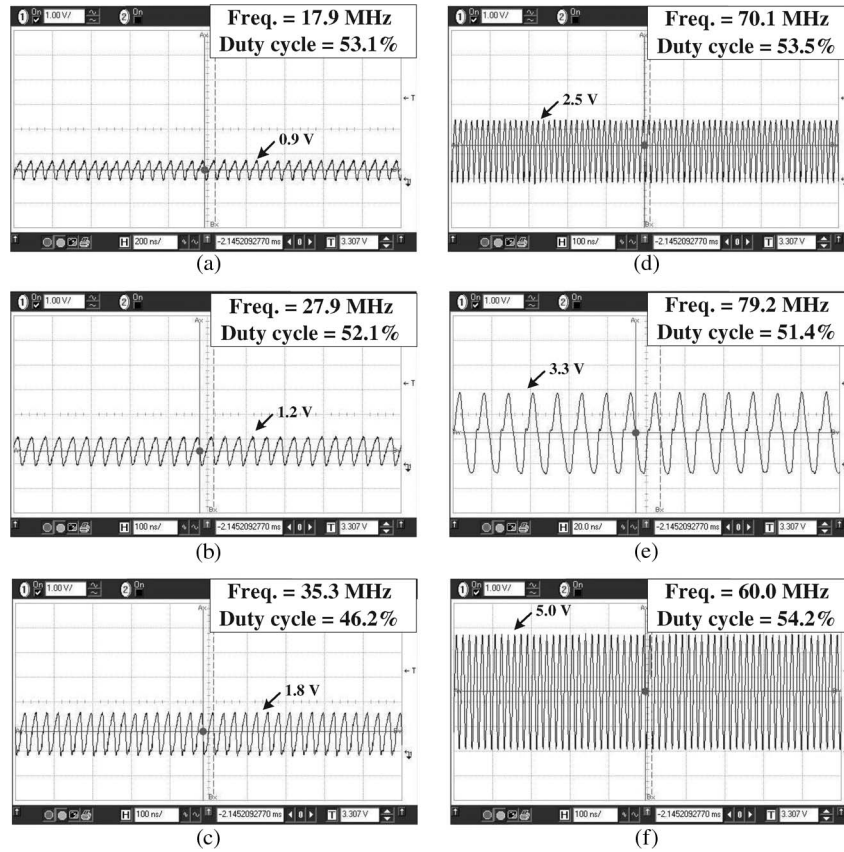


Fig. 5. Measured waveforms of the output signal V_{PAD} at the maximum frequency for different VDDIOs. (a) VDDIO = 0.9 V. (b) VDDIO = 1.2 V. (c) VDDIO = 1.8 V. (d) VDDIO = 2.5 V. (e) VDDIO = 3.3 V. (f) VDDIO = 5.0 V.

TABLE I
COMPARISON WITH SEVERAL PRIOR WORKS

	[5]	[6]	[8]	[10]	[11]	This work
# of voltage modes	2	2	1	1	3	6
Tx VDDH	No	No	Yes	Yes	Yes	Yes
Tx VDDL	No	No	No	No	Yes	Yes
Rx VDDH	Yes	Yes	No	No	Yes	Yes
Rx VDDL	No	No	No	No	Yes	Yes
Max. operating voltage	2-VDD	3-VDD	3.3-VDD	3-VDD	1.5-VDD	1.5-VDD
Min. operating voltage	VDD	VDD	3.3-VDD	3-VDD	0.54-VDD	0.27-VDD
Output stage	1P2N	1P1N	2P2N	3P3N	2P2N	2P2N
Thick-oxide	No	No	Yes	No	No	No
Normal Voltage (VDD)	2.5 V	1.0 V	1.0 V	2.5 V	3.3 V	3.3 V
Process	0.25 μm	0.13 μm	0.13 μm	0.25 μm	0.35 μm	0.35 μm
Area (mm^2)	N/A	0.0105	0.0316	5.76	0.0336	0.0497
Year	2006	2006	2007	2005	2009	2009

voltage for output PMOS and NMOS, the proposed I/O buffer can generate output the signal with 54.2% duty cycle in the worst case. In addition, the power consumption of the proposed design is only 553 nW by using the low-power clamping bias circuit.

ACKNOWLEDGMENT

The authors would like to thank the Chip Implementation Center, National Applied Research Laboratories, Taiwan, for their thoughtful chip fabrication service, and K.-C. Huang with Himax Technologies, Inc., for the fruitful suggestions.

REFERENCES

[1] H. Ballan and M. Declercq, *High Voltage Devices and Circuits in Standard CMOS Technologies*. Norwell, MA: Kluwer, 1999.
 [2] E. J. Mentze, H. L. Hess, K. M. Buck, and T. G. Windley, "A scalable high-voltage output driver for low-voltage CMOS technologies," *IEEE Trans. Very Large Scale Integr. (VLSI) Syst.*, vol. 14, no. 12, pp. 1347–1353, Dec. 2006.

[3] C.-H. Chuang and M.-D. Ker, "Design on mixed-voltage-tolerant I/O interface with novel tracking circuits in a 0.13- μm CMOS technology," in *Proc. IEEE Int. Symp. Circuits Syst.*, May 2004, vol. 2, pp. 577–580.
 [4] M. J. M. Pelgrom and E. C. Dijkmans, "A 3/5 V compatible I/O buffer," *IEEE J. Solid-State Circuits*, vol. 30, no. 7, pp. 823–825, Jul. 1995.
 [5] M.-D. Ker, S.-L. Chen, and C.-S. Tsai, "Overview and design of mixed-voltage I/O buffers with low-voltage thin-oxide CMOS transistors," *IEEE Trans. Circuits Syst. I, Reg. Papers*, vol. 53, no. 9, pp. 1934–1945, Sep. 2006.
 [6] M.-D. Ker and S.-L. Chen, "Design of mixed-voltage I/O buffer by using NMOS-blocking technique," *IEEE J. Solid-State Circuits*, vol. 41, no. 10, pp. 2324–2333, Oct. 2006.
 [7] H.-W. Tsai and M.-D. Ker, "Design of 2VDD-tolerant I/O buffer with considerations of gate-oxide reliability and hot-carrier degradation," in *Proc. 14th IEEE ICECS*, Dec. 2007, pp. 1240–1243.
 [8] S.-L. Chen and M.-D. Ker, "An output buffer for 3.3-V applications in a 0.13- μm 1/2.5-V CMOS process," *IEEE Trans. Circuits Syst. Part II—Exp. Briefs*, vol. 54, no. 1, pp. 14–18, Jan. 2007.
 [9] A.-J. Annema, G. J. G. M. Geelen, and P. C. de Jong, "5.5-V I/O in a 2.5-V 0.25- μm CMOS technology," *IEEE J. Solid-State Circuits*, vol. 36, no. 3, pp. 528–538, Mar. 2001.
 [10] B. Sermeels, T. Piessens, M. Steyaert, and W. Dehaene, "A high-voltage output driver in a 2.5-V 0.25- μm CMOS technology," *IEEE J. Solid-State Circuits*, vol. 40, no. 3, pp. 576–583, Mar. 2005.
 [11] T.-J. Lee, T.-Y. Chang, and C.-C. Wang, "Wide-range 5.0/3.3/1.8 V I/O buffer using 0.35- μm 3.3-V CMOS technology," *IEEE Trans. Circuits Syst. Part I—Reg. Papers*, vol. 56, no. 4, pp. 763–772, Apr. 2009.
 [12] M.-D. Ker and C.-H. Chung, "Electrostatic discharge protection for design for mixed-voltage CMOS I/O buffers," *IEEE J. Solid-State Circuits*, vol. 37, no. 8, pp. 1046–1055, Aug. 2002.
 [13] M.-D. Ker and C.-S. Tsai, "Design of 2.5 V/5 V mixed-voltage CMOS I/O buffer with only thin oxide device and dynamic n-well bias circuit," in *Proc. IEEE Int. Symp. Circuits Syst.*, May 2003, vol. 5, pp. V-97–V-100.
 [14] M.-D. Ker, T.-M. Wang, and F.-L. Hu, "Design on mixed-voltage I/O buffers with slew-rate control in low-voltage CMOS process," in *Proc. 15th Int. Conf. Electron., Circuits Syst.*, Aug. 2008, pp. 1047–1050.
 [15] T.-J. Lee, W.-C. Chang, and C.-C. Wang, "Mixed-voltage I/O buffer using 0.35 μm CMOS technology," in *Proc. IEEE Int. Conf. Electron., Circuits Syst.*, Aug. 2008, pp. 850–853.